# Advanced Magnetics

# For 125-mm ID targets

The most versatile rotary magnet system available, Sputtering Components Advanced Magnetics for 125-mm ID targets are designed to provide high quality, uniform coatings for your application.

- Designed using 3D finite element analysis software - for meeting your application requirements
- Carefully matched, high-strength magnets that are factory calibrated using an automated magnet bar measurement tool - for uniform coatings
- Fully encapsulated magnets and robust construction - for many years of trouble-free operation
- Long-life, multi-roller system for reliable sputter up, sputter down or offangle sputtering
- Magnetic positioning points that are easily set using simple tools - for easy uniformity adjustment
- A simple installation procedure with solutions for vertical installation and connecting to end blocks from other manufacturers

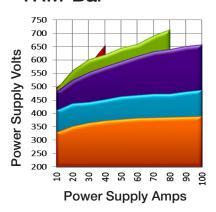


		TECHNICAL SPECIFICATIONS				
Maximum Target Diameter	Gauss (Typical)	Sputter Angle	Patented Turnaround*	Application		
) 160 mm	540	± 12°	No	Standard targets, most materials		
) 170 mm	620	± 15°	Yes	Thicker targets, high material utilization		
180 mm	870	± 21°	Yes	Thickest targets, ITO, electrical grade film		
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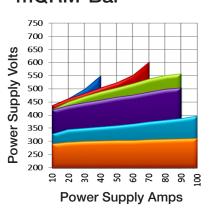
<sup>\*</sup>Improves target utilization



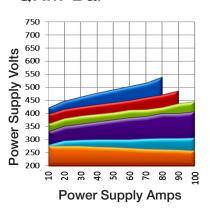
#### TRM-Bar™



## mQRM-Bar™



## QRM-Bar™



ODs, from bottom to top:



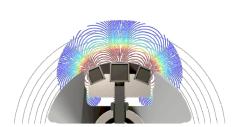
145 mm

155 mm

160 mm

165 mm

175 mm



- Small magnet, three-row design
- Narrowest deposition profile minimizes coating loss to shields
- Multiple turn-around design options specific to your application
- Easy change turn-arounds



- Small magnet, four-row design
- Patented staggered turn-around design for better target utilization
- Improved performance and reduced impedance
- Stable plasma impedance over the target life



- Large magnet, four-row design
- Patented staggered turn-around design for better target utilization
- Improved performance
- Best plasma impedance stability over the target life

